

ABSTRACT OF THE DISCLOSURE

Thermophoresis within lithography systems for protecting reticles from contaminants (e.g., floating particles). Generally, thermophoretic protection is implemented by maintaining the reticle at a higher temperature than its surrounding environment. Thermophoretic protection can be maintained throughout a reticle's use in a lithography system. For example, a reticle can be thermophoretically protected while in storage, through various stages of transportation via a reticle handler (also referred to as an end-effector), to its period of use while attached to a reticle chuck.